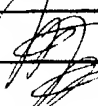
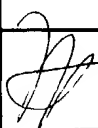
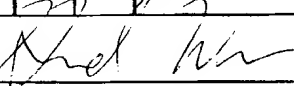


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FILING DATE August 14, 2001				GROUP 2814				
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
	AA	5,736,670	4/7/1998	Carbonell et al.				
	AB	6,297,129 B2	10/02/01	Tran et al.				
	AC							
	AD							
	AE							
	AF							
	AG							
	AH							
	AI							
	AJ							
	AK							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
	AL							
	AM							
	AN							
	AO							
	AP							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR		Faxon et al., "A Highly Manufacturable Trench Isolation Process for Deep Submicron DRAMs," ©1993 IEEE, 4 pages.					
	AS							
	AT							
EXAMINER 				DATE CONSIDERED 12/2/03				
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